

REMARKS

Claims 1, 2 and 4-5 are pending and under consideration in the above-identified application and Claims 3 and 6 were previously cancelled.

In the Office Action, Claims 1, 2 and 4- 5 were rejected.

In this Amendment, Claim 1 is amended. No new matter has been introduced as a result of this Amendment.

Accordingly, Claims 1, 2, 4 and 5 remain at issue.

I. 35 U.S.C. § 103 Obviousness Rejection of Claims 1-2 and 4-6

Claims 1-2 and 4-6 were rejected under 35 U.S.C. § 103(a) as being unpatentable over *Tsuda et al.* (“*Tsuda*”) (U.S. Patent No. 5,936,688) in view of *Nakamura et al.* (“*Nakamura*”) (U.S. Patent No. 5,847,789), and in further view of *Itoh et al.* (“*Itoh*”) (U.S. Patent No. 6,094,252).

Although, Applicants respectfully traverse this rejection, to further prosecution, Claim 1 has been amended to clarify the invention and remove any ambiguities that may have been at the basis of this rejection.

Claim 1 is directed to a method of manufacturing a diffusing reflector.

In the relevant part, Claim 1 recites

“forming an uneven surface layer having the maximum inclination angle of under 12° by coating with a thin layer of a second resin said gently deformed pillar-shaped bodies;

covering with the second resin open flat spaces located between said isolated adjacent pillar-shaped bodies to form one concave gap between any two adjacent isolated pillar-shaped bodies so that upper end portions of said any two adjacent isolated pillar-shaped bodies are higher than a lower end portion of said one concave gap in the thickness direction of the diffusing reflector, thereby minimizing an occurrence of a flat surface area on said substrate; and

....

said first resin film is patterned by straight connected lines that form a continuous polygonal pattern, said straight connected lines providing a continuous and substantially uniform gap between any two of said adjacent polygonal pillar-shaped bodies thereby forming a rectilinear honeycomb-like pattern,

said gap is substantially constant throughout the honeycomb-like pattern and has a size equal to about a minimum resolution of said photolithography, and a thickness of the second resin is about 500nm.”

Referring to Applicants' Figure 1D, a second resin 12 is provided as a thin layer on the gently deformed pillar-shaped bodies and as a thicker layer on the open flat spaces located between the isolated adjacent pillar-shaped bodies 11 to form one concave gap between any two adjacent isolated pillar-shaped bodies, thereby minimizing an occurrence of a flat surface area on the substrate. Further as illustrated in Applicants' Figure 2, adjacent pillar-shaped bodies are isolated from each other by a continuous and substantially uniform gap thereby forming a rectilinear honeycomb-like pattern. The width or size of the gap, which is substantially constant throughout the honeycomb-like pattern between any two adjacent polygonal pillar-shaped bodies, is set to about 1 μ m which is almost equal to the minimum resolution of the photolithography process.

This is clearly unlike *Tsuda*, *Nakamura*, and *Itoh* taken singly or in combination with each other.

The Examiner states that *Tsuda* discloses a resin film (34a) used to cover the open flat spaces located between the isolated adjacent pillar-shaped bodies (32c), and points to Column 13, lines 33 – 40 for support. However, as illustrated in at least FIGs. 5A - 5I of *Tsuda*, the resin film 34a is provided only in these open flat spaces, but no thin layer of the resin film 34a is deposited on any of these pillar-shaped bodies 32c, as required by Claim 1.

Moreover, as illustrated in at least Figures 6G - 6J, 9H - 9L, 20H - 20L, and 21G - 21J, in *Tsuda* the pillar-shaped bodies 32c, being either circular or polygonal, are much sparsely and unevenly distributed on the supporting substrate to form a rectilinear honeycomb-like pattern, which is characterized by a continuous and substantially uniform concave gap between any two adjacent pillar-shaped bodies having a substantially constant size equal to about a minimum resolution of the processing photolithography, as required by Claim 1.

Further, *Nakamura* and *Itoh*, taken individually or in any combination with each other, also fail to teach or suggest the second resin is provided to coat as a thin layer the gently deformed pillar-shaped bodies and to cover open flat spaces located therebetween, and the formation of the rectilinear honeycomb-like pattern, as required by Claim 1.

Thus, Claim 1 is patentable in view of *Tsuda*, *Nakamura*, and *Itoh*, as are dependent Claims 2, 4 and 5, for at least the same reasons.

II. Conclusion

In view of the above amendments and remarks, Applicant submits that Claims 1, 2, 4 and 5 are clearly allowable over the cited prior art, and respectfully requests early and favorable notification to that effect.

If the claims are not found to be in condition for allowance, the Examiner is requested to contact the undersigned to schedule an interview before the mailing of the Office Action. Any communication initiated by this paragraph should be deemed an Applicant initiated interview.

Respectfully submitted,

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